Photoluminescence of ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) Thin Films

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Mn-doped ZnGa₂O_{4-x}M_x (M=S, Se) thin film phosphors have been grown using a pulsed laser deposition technique under various growth conditions. The structural characterization carried out on a series of ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) films grown on MgO(100) substrates using Zn-rich ceramic targets. Oxygen pressure was varied from 50 to 200 mTorr and Zn/Ga ratio was the function of oxygen pressure. XRD patterns showed that the lattice constants of the ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) thin film decrease with the substitution of sulfur and selenium for the oxygen in the ZnGa₂O₄. Measurements of photoluminescence (PL) properties of ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) thin films have indicated that MgO(100) is one of the most promised substrates for the growth of high quality ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) thin films. In particular, the incorporation of Sulfur or Selenium into ZnGa₂O₄ lattice could induce a remarkable increase in the intensity of PL. The increasing of green emission intensity was observed with ZnGa₂O_{3.925}Se_{0.075}:Mn²⁺ and ZnGa₂O_{3.925}S_{0.05}:Mn²⁺ films, whose brightness was increased by a factor of 3.1 and 1.4 in comparison with that of ZnGa₂O₄:Mn²⁺ films, respectively. These phosphors may promise for application to the flat panel displays.

Keywords: Photoluminescence, Thin film, Pulsed laser ablation, ZnGa₂O₄:Mn²⁺

1. INTRODUCTION

For the development of flat panel display devices, such as field emission displays (FEDs), plasma display panels (PDPs), and thin-film electroluminescent devices, highly efficient phosphor materials has been required. Recently, zinc gallate (ZnGa₂O₄) and Mn-doped ZnGa₂O₄ have attracted enormous attention applications in vacuum fluorescent display (VFD) and field emission display (FED) as a low-voltage cathodoluminescence phosphor[1-4]. ZnGa₂O₄ has a spinel structure with space group of Fd_{3m} and an energy band gap of about 4.4 eV and shows blue photoluminescence without doping via transition of a self-activated center. In normal spinel structure, Zn²⁺ ions occupy the tetrahedrally coordinated sites, whereas Ga³⁺ ions occupy the octahedrally coordinated sites. Jeong et al[5]. did report the new self-activated optical center in ZnGa₂O₄ related to tetrahedrally coordinated Ga-O groups. The emission shifts to green by activation with Mn²⁺ ions in tetrahedral host lattice sites[3]. The green emitting Mn²⁺ site in ZnGa₂O₄:Mn²⁺ is generally accepted as tetrahedrally coordinated, but there are two kinds of ions which are tetrahedrally coordinated where Mn²⁺ ions can be replaced in ZnGa₂O₄[5]. A given optical center in different host lattice will exhibit different optical properties due to the changes of the direct surroundings of the center. When we substitute

oxygens with sulfurs or selenium in $ZnGa_2O_4$, i.e., $ZnGa_2O_{4-x}M_x$ (M=S, Se), we can expect some changes on its optical properties.

Among the several thin film deposition techniques, pulsed laser deposition has been eagerly used for high quality ZnGa₂O₄ thin films[6-8]. Thin film phosphors have several advantages over powders, such as higher lateral resolution from smaller grains, better thermal stability, reduced outgassing, and better adhesion to the solid surface[9]. However, the biggest hindrance in the use of phosphors in thin films form is their low brightness and efficiencies in comparison to those of bulk powder materials.

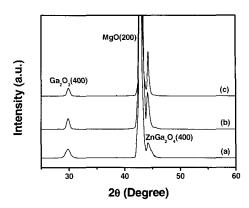
Although numerous studies have been performed to improve the luminescent intensity of phosphor materials, fundamental relationship between structural properties and luminescent characteristics in thin film phosphors is not fully understood. In this study, we will investigate the characteristics of luminescence for the ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) phosphor thin films that are fabricated by pulsed laser deposition (PLD) on MgO (100) substrates. By changing the fabrication conditions and the concentrations of dopants (M=S, Se), we will measure the crystallinity, and surface morphology and PL spectrum and analyze the relationship between the fabrication conditions and characteristics of luminescence. Therefore, we could develop the superior phosphors that improve the luminescent efficiency.

2. EXPERIMENTAL

Zn-rich $ZnGa_2O_{4-x}M_x:Mn^{2+}$ (M=S, Se) powder samples (2ZnO + 1.5Ga₂O₃) were synthesized through solid state reactions of ZnO[Alfa, 99.999%], Ga₂O₃[Alfa, 99.999%], elemental sulfur or selenium and MnO in the evacuated quartz tube at 1000 °C for 12 hours in an electric furnace. To compensate for the loss of Zn ions during the deposition, the Zn-rich powder samples were used. The doping mole fraction of Mn²⁺ in the Zn-rich ZnGa₂O_{4-x}M_x (M=S, Se) powder was fixed at 0.02, and the x value in ZnGa₂O_{4-x}S_x and ZnGa₂O_{4-x}Se_x was 0.05 and 0.075, respectively. The films were grown by pulsed laser ablation using an excimer ArF laser with a wavelength of 193 nm. The beam of excimer laser was focused on the surface of Zn-rich ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) ceramic targets (with 1 inch diameter, and hot pressed and thermally annealed) with a spot size of about $1 \text{ mm} \times 2.5 \text{ mm}$. The distance between target and substrate was kept at about 40 mm. The laser fluence was approximately 3.5 J/cm² and repetition rate used was 5 Hz. The oxygen growth pressure was varied from 50 to 200 mTorr. A variety of characterization techniques were employed to study various properties of the as-grown $ZnGa_2O_{4-x}M_x:Mn^{2+}$ (M=S, Se) films, including a x-ray diffraction (XRD) for film structure, atomic force microscope (AFM) for surface morphology and roughness. The PL spectra were measured at room temperature using a broadband incoherent ultraviolet (UV) light excitation source with a dominant wavelength of 232 nm.

3. RESULTS AND DISCUSSION

Figure 1 shows the XRD patterns as-grown $ZnGa_{2}O_{4}:Mn^{2+},\ ZnGa_{2}O_{3.95}S_{0.05}:Mn^{2+}\ and\ ZnGa_{2}O_{3.925}$ Se_{0.075}:Mn²⁺ films deposited on MgO (100) substrates at oxygen pressure 100 mTorr and substrate temperature 600 °C. The ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) films were perfectly crystallized. ZnGa₂O₄ has a spinel cubic structure (a = 0.8335 nm) and the lattice mismatch is less than 1 % with MgO (a = 0.4211 nm). Epitaxial films were certainly obtained on MgO (100) substrates under certain deposition conditions due to the low lattice mismatch. The x-ray θ -2 θ scan in Fig. 1 shows the crystalline orientation for epitaxial films grown on (100) MgO at 600 °C. The XRD patterns of films reveal a (400) ZnGa₂O₄ diffraction peak at 44° with an additional diffraction peak near 30°, which is likely associated with a (400) Ga₂O₃ phase. As can be seen from this figure, Zn loss was observed in the $ZnGa_2O_{4-x}M_x:Mn^{2+}$ (M=S, Se) films deposited using a Zn-rich ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) ceramic targets due to the relatively high vaporization pressure of Zn. The shift of (400) ZnGa₂O₄ peaks are observed. In the case of ZnGa₂O_{3.925} Se_{0.075}:Mn²⁺ film, the (400) ZnGa₂O₄ diffraction peaks



shift toward larger angles. Also a very small change in lattice constant is observed and the lattice constant of ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) decrease when oxygen is substituted with sulfur (S) or selenium (Se) in ZnGa₂O₄ films. This observation is in contradiction to the ionic radius argument. This result indicates that the substitution of S or Se increases the covalency of ions and then reduces the lattice constant. Two possible variations of the lattice constants occur in the tetrahedral sites in the ZnGa₂O₄ when S, Se and Mn are added. One possibility of the variation is the substitution of oxygen with S or Se in forming tetrahedrons. Another possible change is the sites where the Mn²⁺ ions are located in tetrahedrons, i.e. ZnO₄ or GaO₄[5].

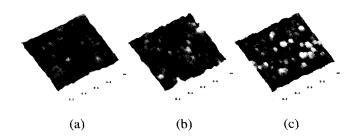
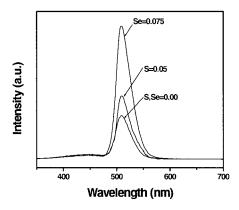


Fig. 2. A comparison of AFM images in as-grown (at 600 °C) $ZnGa_2O_{4-x}M_x:Mn^{2+}$ (M=S, Se) thin films (a) $ZnGa_2O_4:Mn^{2+}$, (b) $ZnGa_2O_{3.95}S_{0.05}:Mn^{2+}$, (c) $ZnGa_2O_{3.925}Se_{0.075}:Mn^{2+}$.

Figure 2 shows the atomic force microscope (AFM) images of as-grown (at 600 °C) thin films (a) $ZnGa_2O_4:Mn^{2+}, \quad (b) \quad ZnGa_2O_{3.95}S_{0.05}:Mn^{2+}, \quad (c) \\ ZnGa_2O_{3.925}Se_{0.075}:Mn^{2+}. \quad Surface morphologies of the <math display="inline">ZnGa_2O_{4-x}M_x:Mn^{2+}$ (M=S, Se) films revealed by an AFM images on a surface area of $1\mu m \times 1\mu m.$ As one can see from these pictures, the variations in morphology are evident for the $ZnGa_2O_{4-x}M_x:Mn^{2+}$ (M=S, Se) films grown with the substitution of S or Se for oxygen in

ZnGa₂O₄ lattice. The surface roughness is very related to the crystallinity and average grain size of the films. According to the results of Fig. 1, when we substituted oxygens with sulfur or selenium, the intensity of (400) diffraction peak increased. The average grain size and roughness are increased due to the improved crystallinity of the films by S or Se doping. Films with different roughnesses were obtained by substituting oxygen with S or Se and the values of root mean square (rms) roughness of ZnGa₂O₄:Mn²⁺, ZnGa₂O_{3.95}S_{0.05}:Mn²⁺ and ZnGa₂O_{3.925}Se_{0.075}:Mn²⁺ measured by AFM, were found to 3.25 nm, 5.43 nm and 10.92 nm, respectively. Roughness of the ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) films had a strong effect on the PL response of the films.



The photoluminescence (PL) spectra of ZnGa₂O₄. $_xM_x:Mn^{2+}$ (M=S, Se) films are shown in Fig. 3. The films exhibit a broad band emission extending from 470 to 550 nm, peaking at 509 nm. The emission band can be primarily attributed to the transition ${}^{4}T_{1} \rightarrow {}^{6}A_{1}$ of the 3d electrons in the Mn²⁺ ion. When we substitute oxygens with S or Se in ZnGa₂O₄, we can expect some changes on its optical properties. A given optical center in different host lattice will exhibit different optical properties due to the changes of the direct surroundings of the center. The emission intensity ZnGa₂O_{3.925}Se_{0.075}:Mn²⁺ films exhibits the strongest among the samples studied in this work. The peak intensity of PL of the ZnGa₂O_{3.925}Se_{0.075}:Mn²⁺ films is about a factor of 3.1 times brighter than that of the ZnGa₂O₄:Mn²⁺ films and enhanced about a factor of 2.1 in comparison with than that ZnGa₂O_{3.95}S_{0.05}:Mn²⁺ films. Thus, since the environment change of the GaO₄ tetrahedron into the Ga₂O_{4-x}M_x (M=S, Se) enhances the Ga³⁺ absorption, the emission intensity consequently increases. The oscillation strength of the $ZnGa_2O_{3.95}S_{0.05}$: Mn^{2+} and $ZnGa_2O_{3.925}Se_{0.075}$: Mn^{2+} films in the absorption of both Ga³⁺ and Mn²⁺ is stronger than that of the ZnGa₂O₄:Mn²⁺ film. This trend that occurs in the absorption leads to the enhancement of the emission intensity[10].

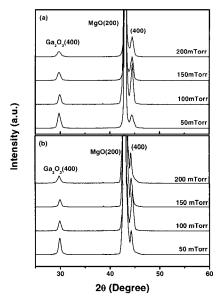


Fig. 4. XRD patterns of (a) $ZnGa_2O_{3.925}Se_{0.075}:Mn^{2+}$ and (b) $ZnGa_2O_{3.95}S_{0.05}:Mn^{2+}$ films as a function of oxygen pressure.

Figure 4 shows the XRD patterns of the as-grown (a) $ZnGa_2O_{3.925}Se_{0.075}:Mn^{2+}$ and (b) $ZnGa_2O_{3.95}S_{0.05}:Mn^{2+}$ films deposited on MgO(100) substrates at the fixed substrate temperature 600 °C with the different oxygen pressures. The oxygen pressure significantly influenced formation of the both films. The films grown under low oxygen pressure reveal a (400) ZnGa₂O₄ peaking at 44 ° with an additional diffraction peak near 30°, which is likely associated with a Ga₂O₃ phase. The variation of Zn/Ga ratio in the films also depends on the oxygen pressure during deposition. Reduced Ga₂O₃ diffraction peak intensity was observed with an increasing oxygen pressure in both films. Introduction of additional oxygen will produce more ZnO molecules through gas-phase collisions of Zn species with oxygen. Increased oxygen pressure reduces the probability of vaporization of Zn species from the heated substrates and results in the incorporation of more Zn in the both films.

Shown in Fig. 5 are the plots of PL intensity and rms roughness of $ZnGa_2O_{3.925}Se_{0.075}:Mn^{2+}$ thin films as a function of oxygen pressure. Note that initially the PL intensity and rms roughness of $ZnGa_2O_{3.925}Se_{0.075}:Mn^{2+}$ films increase linearly with oxygen pressure, while the initial increase on both quantities decreases as the oxygen pressure increases from 100 to 200 mTorr. Maximum PL intensity was observed at an oxygen pressure of 100 mTorr, which relates to the ratio of Zn/Ga and surface roughness of the films. The reduction in PL intensity with reduced $P(O_2) = 50$ mTorr correlates with the too much formation of the Ga_2O_3 phase due to the severe Zn deficiency and lower surface roughness.

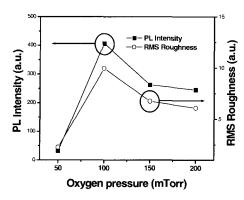


Fig. 5. PL intensity and rms roughness of $ZnGa_2O_{3.925}Se_{0.075}$: Mn^{2+} films as a function of oxygen pressure.

4. CONCLUSIONS

High quality ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) phosphor thin films have been deposited on MgO(100) single crystal substrate using a pulsed laser deposition technique. Zn-rich ceramic targets have been prepared to compensate the Zn loss due to the relatively high vaporization pressure of Zn. The variation of the Zn/Ga ratio in the films depends on the oxygen pressure during deposition. The shift of (400) ZnGa₂O₄ peaks are observed as S or Se substituted the oxygen. For the case of $ZnGa_2O_{4-x}M_x:Mn^{2+}$ (M=S, Se) thin film, the (400) ZnGa₂O₄ diffraction peaks shift toward larger angles. A small change in lattice constant is observed and the lattice constant is shortened in ZnGa₂O_{4-x}M_x:Mn²⁺ (M=S, Se) films. The all films exhibit a broad band emission extending from 470 to 550 nm, peaking at 509 nm. The PL intensity is highly dependent on the crystallinity. surface morphology and a kind of dopant. Especially, the incorporation of S or Se into ZnGa₂O₄ lattice could induce enhanced crystallinity, rougher surface, and a remarkable increase in the intensity of PL. The emission intensity of the ZnGa₂O_{3.925}Se_{0.075}:Mn²⁺ films exhibits the strongest among the samples studied in this work. The peak intensity of PL of the ZnGa₂O_{3.925}S_{0.075}:Mn²⁺ films is enhanced about a factor of 3.1 times in comparison with that of the ZnGa₂O₄:Mn²⁺ films. Growth of as-deposited ZnGa₂O_{3.925}Se_{0.075}:Mn²⁺ thin films with such a high brightness is very encouraging for the application of thin-film phosphors in display technologies.

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